SHEET 1 OF 3

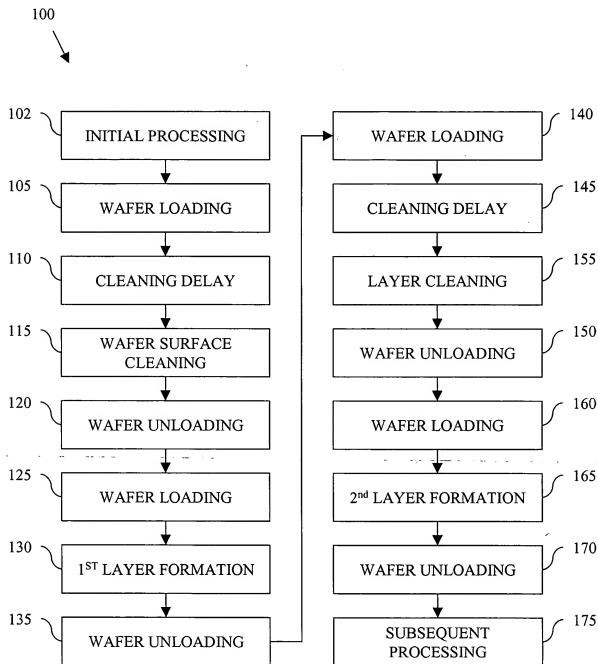


FIGURE 1

Attorney Docket No. 24061.42 SEMICONDUCTOR WAFER MANUFACTURING METHODS EMPLOYING CLEANING DELAY PERIOD SHEET 2 OF 3

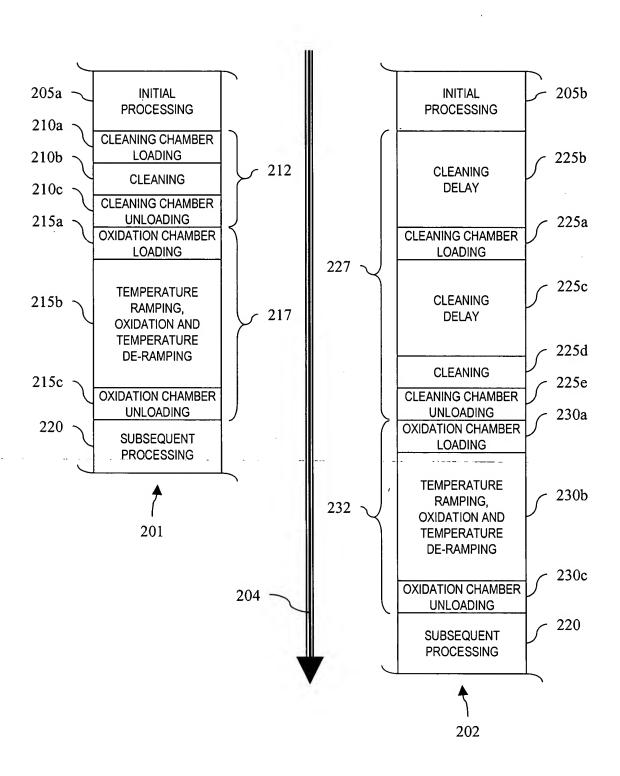


FIGURE 2

Attorney Docket No. 24061.42 SEMICONDUCTOR WAFER MANUFACTURING METHODS EMPLOYING CLEANING DELAY PERIOD

SHEET 3 OF 3

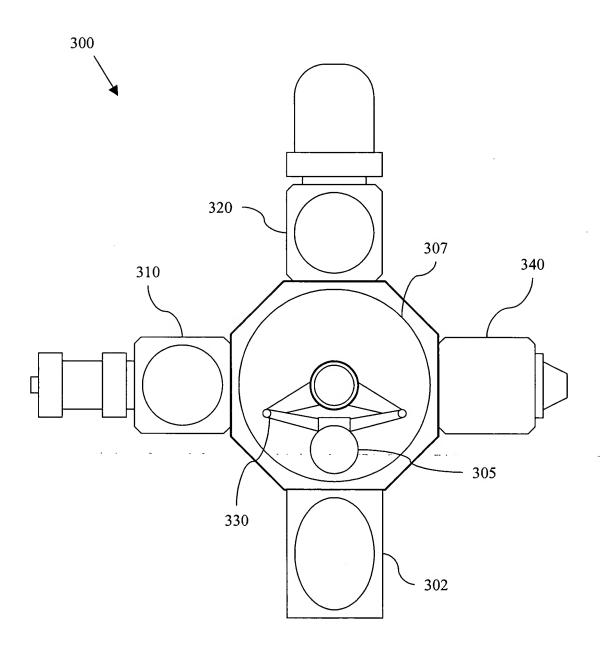


FIGURE 3